Abstract

A FEED-THROUGH APPARATUS FOR A CHEMICAL VAPOUR DEPOSITION DEVICE

A feed-through apparatus for a chemical vapour deposition device is disclosed. The feed-through apparatus includes: i) a feed-through main body; ii) a plurality of runner units; and iii) a feed-through device rotatable with respect to the plurality of runner units. The runner units are provided within the feed-through main body, and each runner unit comprises a fluid inlet for receiving a fluid, and an elongated runner in fluid communication with the fluid inlet for receiving the fluid from the fluid inlet wherein the elongated runner extends spirally on a surface of the runner unit. The feed-through device comprises a plurality of feed-through device fluid channels, which comprise feed-through device fluid transfer orifices for receiving fluids from corresponding elongated runners and feed-through device fluid outlet- orifices for releasing the fluids into a reactor chamber. In particular, each feed-through device fluid transfer orifice is in fluid communication with a corresponding elongated runner during rotation of the feed-through device for receiving fluid from the corresponding elongated runner, and each feed-through device fluid outlet orifice is provided for releasing the fluid into the reactor chamber.

[FIG. 3]